

20 December 2012



TECHNICAL REPORT

CP34531-18AB

Anisotropic Conductive Film for Chip on Glass

Products Development Department Advanced Material Division

Note on the characteristic data given - Data on the characteristics of the products described in this document based on the results of evaluations carried out by the company. This does not guarantee that the characteristics of the product conform with your usage environment. Before use, review the usage conditions based on evaluation data obtained from the equipment and substrates actually used.

Features

-COG application for TFT

-Interconnect a small-to-medium-sized FPD with an IC chip.

-Fine pitch (smaller and Insulated particle) -Low temperature bonding

Specifications

Items		CP34531-18AB	Remarks
Curing system		Epoxy-Cation	*1
Structure and thickness	1) Cover film / color	25µm / transparent	
	2) ACF-layer	8µm	
	3) NCF-layer	10µm	
	4) Base film / color	38µm / white	
Conductive particles	1) Material	Ni plated polymer	
	2) Insulator coated	Yes	
	Particle diameter	3µm	
	Particle density	8.9M pcs/mm ³	Design value. Calculated in ACF later
Minimum overlap area of conductors		1000µm²	(Average -4.5 $\sigma \ge 3pcs$) *2
Minimum bump space		12µm	Space between bumps.
Minimum conductor space		7µm	Space between neighboring circuits.

*1: There is a possibility that interference of cation curing reaction happens depending on the material.(PI layer of IC, Panel with Soda line glass, etc). Confirmation tests of the interference is required on each material.

*2:Where the faced conductor overlaps.

Bonding conditions and Properties

Bonding conditions *1

items		CP34531-18AB	Remarks
ACF laminating conditions	Temperature	50~80°C	*2
	Pressure	0.5 ~ 1.0MPa	*3
	Time	1~2sec	*4
Main bonding conditions	Temperature	150°C~180°C	*2
	Pressure	30~80MPa	*5
	Time	5sec	*4

*1: Bonding condition may differ depending on chip size and metal pattern. We recommend this as a starting point to determine your own optimized conditions.

*2: Temperature of ACF lamination and main bonding: It is not equipment temperature, but actual temperature of ACF.

*3: Pressure of ACF lamination: It is calculated based on the area of ACF lamination.

*4: Time of ACF lamination and main bonding: Time from the start of bonding to the point where the temperature reaches the target.

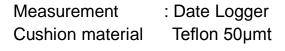
*5: The pressure is calculated based on the total area of bumps.

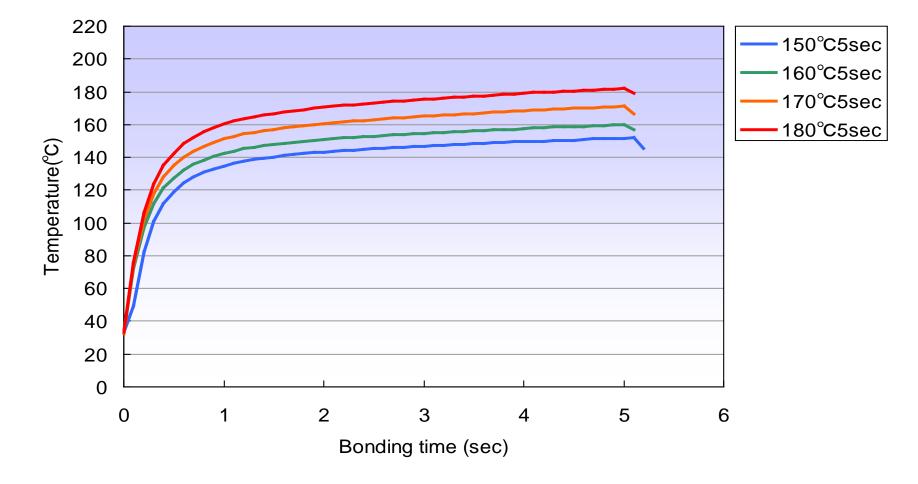
Properties of cured ACF

items		CP34531-18AB	Remarks
Elastic modulus	at 30°C	2.7GPa	DMA
Glass transition temperature (Tg)		154°C	DMA, tan δ peak



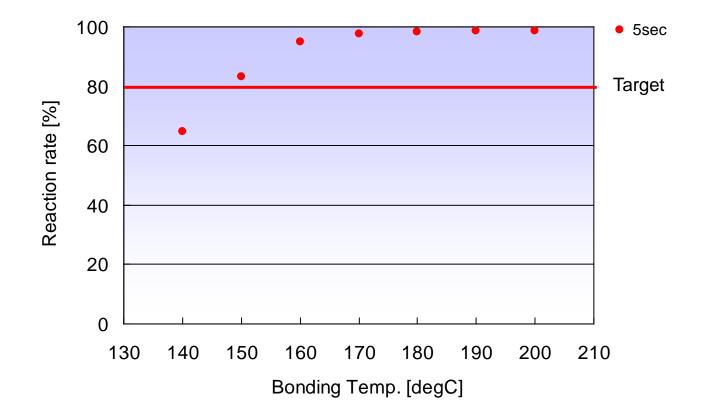
Bonding temperature profile





Reaction rate





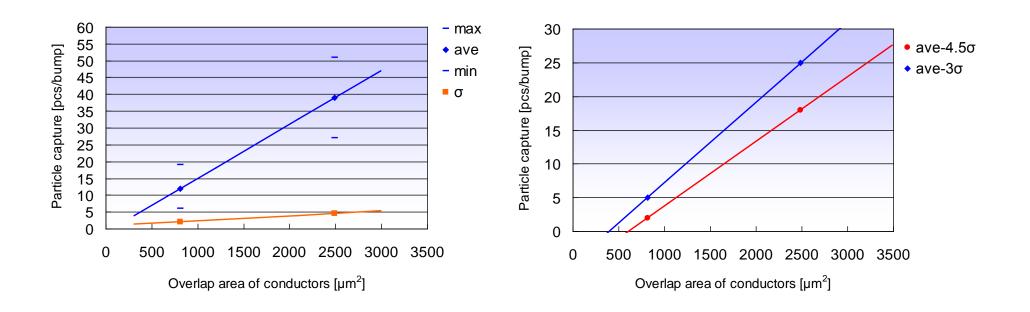
Note: This report has been prepared on the basis of our reliable tests, however is not intended to guarantee the performance described hereunder.

TO BE KEPT SECRETS FROM OUTSIDERS

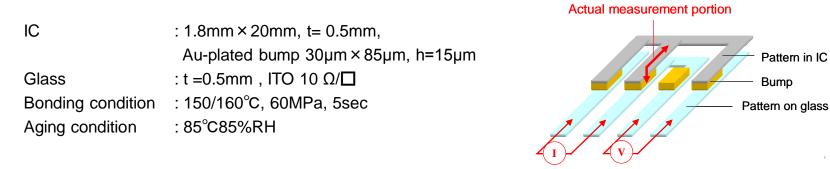


Particle capture

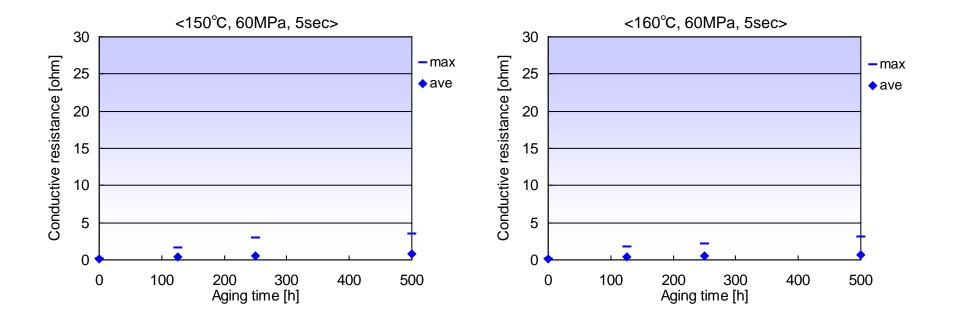
IC: 1.8mm × 20mm, t= 0.5mm,
Au-plated bump, h=15 μ mGlass: t =0.7mm , ITO 10 Ω/\Box Bonding condition: 170°C, 60MPa, 5secMeasurement: 100bumps



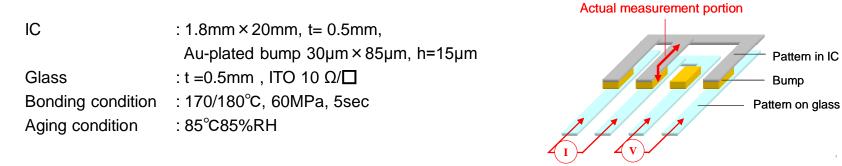
Conductive resistance



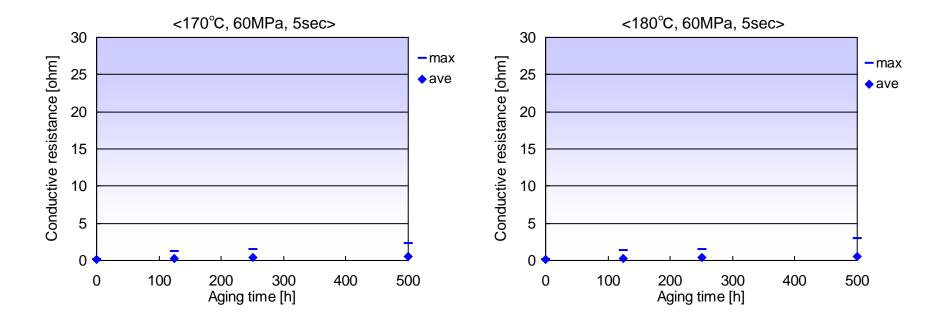
Current input Voltage measurement



Conductive resistance



Current input Voltage measurement





Insulation resistance

